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(54) INORGANIC POWDER-CONTAINING PHOTSENSITIVE RESIN COMPOSITION AND PATTERN FORMING METHOD

(57)Abstract:

PROBLEM TO BE SOLVED: To form a pattern with high reproducibility by using (meth)acrylate of a compd. having a specified number of alkylene oxide groups as repeating units as the photopolymerizable monomer component of an inorg. powder-contg. photosensitive resin compsn.

SOLUTION: In the inorg. powder-contg. photosensitive resin compsn. contg. a polymer binder, a photopolymerizable monomer, a photopolymn. initiator, inorg. powder and an org. solvent, the photopolymerizable monomer is (meth) acrylate of a compd. having 2-9 alkylene oxide groups as repeating units on the average. When a pattern is formed by photolithography, the number of the repeating units is preferably 3-7 on the average. The photopolymerizable monomer is preferably contained by 30-300 pts.wt. based on 100 pts.wt. of the entire photosensitive resin compsn. Other monomer may be added by <20 pts.wt. based on 100 pts.wt. of the photopolymerizable monomer.

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